

Press Release

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Nanonex delivered Advanced Nanoimprint Tool NX-B200 to Swinburne University of Technology, Australia

Princeton NJ, October 12, 2012:

Nanonex Corporation, the inventor and world's leading provider in nanoimprint lithography solutions with the longest history, announces the delivery of Nanonex's NX-B200 system to Swinburne University of Technology at Melbourne, Australia.

The Nanonex NX-B200 purchased by Swinburne University of Technology is a compact, cost-effective and versatile sub-10 nm resolution nanoimprint tool, utilizing Nanonex's patented Air Cushion Press™ technology to provide unsurpassed uniformity and yield over the entire substrate. It can eliminate lateral shifting between the wafer and mask and significantly improve the mask life. The NX-B200 also incorporates a fully flexible Smart Sample Holder that accommodates any size of substrate or mask up to the maximum capability including arbitrary shaped geometries.

About Nanonex Corporation

Nanonex is the inventor of NIL, the world's first nanoimprint lithography company, and the world's leading provider of nanoimprint solutions that include equipment,

masks, resists and processes. Nanonex's patented and proprietary NIL solutions and Air-Cushion Press TM can manufacture 3D nanostructures with sub-5 nm resolution, large-area uniformity, accurate overlay alignment, high throughput, and low cost. Nanonex NIL solutions have been adopted by a broad spectrum of applications, such as optical devices, data storage, displays, light emitting diodes, semiconductor ICs, biotech, chemical synthesis, and advanced materials. Nanonex has over 100 customers and an installed base of over 50 tools world-wide. Visit www.nanonex.com for additional information.